

Ätzpasten für anorganische Oberflächen

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Abstract of DE10101926

The invention relates to novel etching media in the form of printable, homogenous, particle-free etching pastes with non-Newtonian flow properties for the etching of inorganic surfaces, in particular, of glasses, preferably on silicon oxide and silicon nitride based glass and other silicon oxide and silicon nitride based systems and layers thereof. The invention further relates to the use of said etching media.

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